



Press Release

Molecular Transfer Lithography Patent Accepted in China

Concerning patents licensed to TDI from Stanford University, international patent coverage is extended for molecular transfer lithography processes and PVA templates

Santa Clara, CA, September 24, 2008 - With patents granted in the U.S. including 6,849,558 and 7,345,002 for the molecular transfer lithography (MxL) processes achieving high resolution nanopatterning with templates that are destroyed as part of the replication procedure, the China patent office has given notification to Stanford University that the fundamental broad patent claims have been accepted. From Stanford, TDI has licensed the patent portfolio associated with the MxL processes and PVA (polyvinyl alcohol) nanostructured templates, including all international filings, and additional divisional patents currently pending.

“In extending to China the strong patent position of the seminal work constituting MxL processing and PVA templates that TDI has obtained through a licensing agreement with Stanford University, this growing patent portfolio provides protection to all stakeholders involved in the commercialization of the MxL/PVA technology, including customers,” stated Charles Schaper, President and CEO of TDI.

About TDI Nanopatterning

With the goal to productize the MxL class of nanopatterning processes that are enabled with water dissolvable templates, of which patents have been granted and licensed, TDI designs, manufactures and market whole product molecular transfer lithography solutions comprising tooling and PVA templates, for applications in nanoelectronics manufacturing and biomedical treatments.

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